

INFORMATION DISCLOSURE STATEMENT

FORM PTO 1449 (modified)

U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICELIST OF REFERENCES CITED BY APPLICANT(S)
(Use several sheets if necessary)

Date Submitted to PTO: July 22, 2008

ATTY DOCKET NO.
2006_0772ASERIAL NO.
10/581,256APPLICANT
Mitsuhiro OKUNE et al.FILING DATE
May 31, 2006GROUP
1765

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	AA	5,871,659	2/1999	Sakano et al.			
	AB	4,214,946	7/1980	Forget et al.			
	AC						
	AD						
	AC						
	AF						

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO
	BA						
	BA						
	AC						
	AD						
	AC						

OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)

CA	Supplementary European Search Report issued <u>June 11, 2008</u> in EP 04 81 9793, which is a foreign counterpart to the present application
CB	Meint J. DE BOER et al., "Guidelines for Etching Silicon MEMS Structures Using Fluorine High-Density Plasmas at Cryogenic Temperatures", JOURNAL OF MICROELECTROMECHANICAL SYSTEMS IEEE Service Center, Piscataway, NJ, vol. 11, no. 4, August 1, 2002 (8/1/2002)
CC	Seiji SAMUKAWA et al., "Effects of Discharge Frequency in Plasma Etching for Ultra large-Frequency Plasma Source for High-Performance Etching for Ultra large-Scale Integrated Circuits", JAPANESE JOURNAL OF APPLIED PHYSICS, Japan, Society of Applied Physics, Tokyo, Japan, vol. 39, no. 4A, Part 01, April 1, 2000 (4/1/2001)
CD	

EXAMINER

DATE CONSIDERED